

Abstract

A With view to provide a method and equipment for detecting
A a minute circuit pattern with high resolution, pattern defect
A detecting equipment is ~~constructed~~ ^{provided}, comprising: an ultraviolet
laser source; coherence reducing means for reducing the coherence
of the ultraviolet laser beam emitted from this ultraviolet laser
source; projecting means for projecting the ultraviolet laser
beam passing through this coherence reducing means on a pupil of
an objecting lens; illuminating means for illuminating a detection
field of view in the object uniformly by the ultraviolet laser beam
projected on the pupil of the objective lens by this projecting
means through the objective lens; image detecting means for
detecting an image of the object illuminated almost uniformly by
the illuminating means; and detecting means for detecting a
defect on the object by comparing image data obtained from the
image of the object detected by this image detecting means to
image data stored beforehand.